	Hits	Search Text	DBs
7	1	((organic or polymer$4 or polyimide) same (conductive or electroconductive or semiconduct$4) same (dop$4 or implant$4 or infus$3) same (irradiat$4 or expos$4 or illuminat$4) same (UV or IR or DUV or EUV or excimer or laser or light or radiation)) and (step$5 or (step$4 near9 repeat) or (selectiv$5 near12 expos$4) or lithograph$6 or irradiat$4 or illuminat$4) and (photomask or mask or reticle or pattern$5) and ((non$4transmissive or opaque or light$6shield$4 or non$4transparent) same (region or space$2 or area or portion)) and (transmissiv$3 or transparent or transmit$4) and ((dop$4 or implant$6) near22 (UV or irradiat$4 or radiation or exops$4)) and ((remov$6 or etch$6) same (weak or (less$3 near16 (dop$4 or implant$4)) or unbound$4 or non$3bond$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	25	((organic or polymer$4 or polyimide or polyamide or photoresist or resist) same (conductive or electroconductive or semiconduct$4) same (dop$4 or implant$4 or infus$3) same (irradiat$4 or expos$4 or illuminat$4) same (UV or IR or DUV or EUV or excimer or laser or light or radiation)) and (step$5 or (step$4 near9 repeat) or (selectiv$5 near12 expos$4) or lithograph$6 or irradiat$4 or illuminat$4) and (photomask or mask or reticle or pattern$5) and ((dop$4 or implant$6) near22 (UV or irradiat$4 or radiation or exops$4)) and ((remov$6 or etch$6) same (weak or (less$3 near16 (dop$4 or implant$4)) or unbound$4 or non$3bond$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB